

Titles of Most Frequently Occurring Classifications of Patents Returned
From A Search of 09698497 on October 25, 2001

3 438/692 (0 OR, 3 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/689 CHEMICAL ETCHING

438/690 .Combined with the removal of material by
nonchemical means (e.g., ablating, abrading, etc.)

438/691 ..Combined mechanical and chemical material
removal

438/692 ...Simultaneous (e.g., chemical-mechanical
polishing, etc.)

2 318/609 (0 OR, 2 XR)

Class 318 : ELECTRICITY: MOTIVE POWER SYSTEMS

318/560 POSITIONAL SERVO SYSTEMS (E.G.,
SERVOMECHANISMS)

318/609 ."Reset" systems (P.I.)

2 330/252 (0 OR, 2 XR)

Class 330 : AMPLIFIERS

330/250 WITH SEMICONDUCTOR AMPLIFYING DEVICE (E.G.,
TRANSISTOR)

330/252 .Including differential amplifier

2 365/201 (0 OR, 2 XR)

Class 365 : STATIC INFORMATION STORAGE AND RETRIEVAL

365/189.01 READ/WRITE CIRCUIT

365/201 .Testing

2 438/424 (2 OR, 0 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/400 FORMATION OF ELECTRICALLY ISOLATED LATERAL
SEMICONDUCTIVE STRUCTURE

438/424 .Grooved and refilled with deposited dielectric
material

2 438/427 (0 OR, 2 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/400 FORMATION OF ELECTRICALLY ISOLATED LATERAL
SEMICONDUCTIVE STRUCTURE

- 438/424 .Grooved and refilled with deposited dielectric material
- 438/427 ..Refilling multiple grooves of different widths or depths
- 2 438/435 (0 OR, 2 XR)
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
 - 438/400 FORMATION OF ELECTRICALLY ISOLATED LATERAL SEMICONDUCTIVE STRUCTURE
 - 438/424 .Grooved and refilled with deposited dielectric material
 - 438/435 ..Multiple insulative layers in groove
- 2 438/443 (0 OR, 2 XR)
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
 - 438/400 FORMATION OF ELECTRICALLY ISOLATED LATERAL SEMICONDUCTIVE STRUCTURE
 - 438/439 .Recessed oxide by localized oxidation (i.e., LOCOS)
 - 438/443 ..Etchback of recessed oxide
- 2 438/700 (0 OR, 2 XR)
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
 - 438/689 CHEMICAL ETCHING
 - 438/694 .Combined with coating step
 - 438/700 ..Formation of groove or trench
- 2 438/701 (0 OR, 2 XR)
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
 - 438/689 CHEMICAL ETCHING
 - 438/694 .Combined with coating step
 - 438/700 ..Formation of groove or trench
 - 438/701 ...Tapered configuration
- 2 438/702 (0 OR, 2 XR)
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
 - 438/689 CHEMICAL ETCHING
 - 438/694 .Combined with coating step
 - 438/700 ..Formation of groove or trench
 - 438/702 ...Plural coating steps

2 438/792 (0 OR, 2 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/758 COATING OF SUBSTRATE CONTAINING SEMICONDUCTOR
REGION OR OF SEMICONDUCTOR SUBSTRATE

438/778 .Insulative material deposited upon
semiconductive substrate

438/791 ..Silicon nitride formation

438/792 ...Utilizing electromagnetic or wave energy
(e.g., photo-induced deposition, plasma, etc.)

2 438/793 (0 OR, 2 XR)

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2 700/83 (2 OR, 0 XR)

Class 700 : DATA PROCESSING: GENERIC CONTROL SYSTEMS OR
SPECIFIC APPLICATIONS

700/1 GENERIC CONTROL SYSTEM, APPARATUS OR PROCESS

700/83 .Having operator control interface (e.g.,
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Cross-Reference Classifications

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PLUS Search Results for S/N 09698497, Searched October 25, 2001

6169808
6175279
6084474
6208581
5019736
5222043
5640534
5914885
6069956
6131044
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